APAC SILICIDE 2016 Poster Session

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Poster Session I

[17-P1]

Low Cost Fabrication of Mg₂Si Thermoelectric Device with Reused-silicon

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[17-P2]

The Formation and Properties of BaSi₂ Thin Films Obtained by Solid Phase Epitaxy on Si (111) D.V. Fomin¹, V.L. Dubov¹, K.N. Galkin², N.G. Galkin², R.I. Batalov³ and V.A. Shustov³

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[17-P3]

An Influence of Stresses in CaSi₂ hR6 Lattice with R-3m Space Group on the Band Structure and Properties of *h*-CaSi₂/Si and Si/*h*-CaSi₂/Si Heterostructures

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[17-P4]

Thermoelectric Properties of Quaternary Si Clathrate K₈Ga_xZn_ySi_{46-x-y} Shiva Kumar Singh and Motoharu Imai *National Institute for Materials Science, Japan.*

[17-P5]

Energetic Consideration of Compounds Formed at Mg₂Si/Ni Electrode Boundary Layer Yoji Imai¹, Hiroharu Sugawara², Yoshihisa Mori³, Shigeyuki Nakamura⁴, Atsushi Yamamoto¹, and Ken-ichi Takarabe³

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[17-P6]

Formation and Analysis of GeSn on Insulator with Non-Thermal Equilibrium Sn Concentration Obtained by Pulsed Laser-Annealing

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[17-P7]

Enhancement of Hole Concentration in B-doped BaSi₂ Epitaxial Thin Films by Pulse Laser Annealing M. Emha Bayu, H. Urai, D. Tsukahara, K. Toko, T. Makimura, T. Suemasu *Institute of Applied Physics, University of Tsukuba, Japan*

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[17-P8]

p-BaSi₂/n-Si Solar Cells with Conversion Efficiency Approaching 10% by Reduction of Contact Resistance and Surface Passivation using a-Si Capping Layers Suguru Yachi, Ryota Takabe, Kaoru Toko and Takashi Suemasu *Institute of Applied Physics, University of Tsukuba, Japan*

[17-P9]

Synthesis of Si-based Nanostructures by Extraction of Ba Atoms from BaSi₂ in Acid Solutions P. Yuan¹, S. Ksasaki², Y. Kumazawa², H. Tatsuoka²

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[17-P10]

Multi-layer Graphene on Insulator Formed by Co-induced Layer Exchange H. Murata, K. Toko and T. Suemasu *Institute of Applied Physics, University of Tsukuba, Japan*

[17-P11]

Effect of Interlayer on Ag-induced Layer Exchange Crystallization of Amorphous Ge Thin Film on Insulator

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[17-P12]

Observation of pn-junction Depth in Mg₂Si Diodes Fabricated by Short Period Thermal Annealing Yuma Onizawa¹, Tomohiro Akiyama¹, Nobuhiko Hori¹, Fumitaka Esaka², Haruhiko Udono¹ *I Ibaraki University, Japan*

[17-P13]

On the Rod-like Precipitations Formed in the Vapor Deposited Fe-Si Film Shin-ichiro Kondo, Takao Morimura and Hiromichi Nakashima Department of Materials Science and Engineering, Nagasaki University, Japan

[17-P14]

The Crystal Structure and Electrical Resistivity of a Novel Na-Pt-Ge Intermetallic Compound, Na₂Pt₃Ge Kohei Aiba¹, Takahiro Yamada^{1,2}, and Hisanori Yamane¹

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[17-P15]

Preferred Orientation of BaSi₂ Thin Films Fabricated by Thermal Evaporation

Kosuke O. Hara¹, Cham Thi Trinh², Yoshihiko Nakgawa², Yasuyoshi Kurokawa², Keisuke Arimoto¹, Junji Yamanaka¹, Kiyokazu Nakagawa¹, and Noritaka Usami²

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[17-P16]

Synthesis of Flower-like Si Nanostructures on Si Substrates

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[17-P17]

Optical and Photocatalytic Properties of Nanocomposites Composed of Ca_xSi₂ Nano-flakes and Nickel Silicide Particles

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[17-P18]

Mg₂Si/Si Composite Particles Synthesized by a Metathesis Reaction and Their Anode Performance as Li-ion Batteries

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[17-P19]

Syntheses of Si-based Nanostructures Using Silicides as Starting Materials in Acid Solutions Yuki Kumazawa¹, Kenta Sasaki¹, Xiang Meng², Yuan Peiling² and Hirokazu Tatsuoka²

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[17-P20]

Investigation on Minority-carrier Lifetime and Solar Cell Properties of BaSi₂ Formed on Multicrystalline Si Substrates

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[17-P21]

Ion Channeling Measurements of β-FeSi₂ Films Epitaxially Grown on Si(111) and Their Analysis by Multiple Scattering Theory

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[17-P22]

Realization of Crystalline BaSi₂ Thin Films by Vacuum Evaporation on (111)-oriented Si Layers Fabricated by Aluminum Induced Crystallization

Jefferson A. Wibowo¹, Isao Takahashi¹, Kosuke O. Hara² and Noritaka Usami¹

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[17-P23]

Structural Characterizations of Si-based Nanostructures by Extraction of Metallic Atoms from CaSi₂, SrSi₂ and BaSi₂ by Inositol Hexakisphosphate

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Poster Session II

[17-P24]

Preparation of Wire Arrays on Si Substrates by Repeated Chemical Treatment in AgNO₃/HF Aqueous Aolution

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[17-P25]

Synthesis of Mn-based Nanostructures on Mn Substrates

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[17-P26]

Solid-phase Synthesis of Mg₂Si Thin Film on Sapphire Substrate Motomu Saijo, Kazuhiro Kunitake, Ryota Sasajima, Yuta Takagi, Naoyuki Sato, and Takashi Ikehata Graduate School of Science and Engineering, Ibaraki University, Japan

Synthesis of Si-based nanowires on insulating substrates

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Fabrication of Mg₂Si pn-junction Photodiode with Shallow Mesa-structure and Ring Electrode T. Akiyama¹, N. Hori¹, S. Tanigawa², D. Tsuya², H. Udono¹

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[17-P29]

Low Temperature (< 150 °C) Formation of Amorphous Ge on Insulating Substrate by Stress Stimulated Crystallization

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Dependence of Direct Transition Energies on Growth Temperature in β-FeSi₂ Epitaxial Films Motoki Iinuma¹, Hiroaki Tsukamoto², Naoki Murakoso¹, Haruki Yamaguchi² and Yoshikazu Terai¹ ¹ Department of Computer Science and Electronics, Kyushu Institute of Technology, Japan

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Growth of p-type β-FeSi₂ Polycrystalline Films by RF Magnetron Sputtering Shuya Ikeda¹, Kazuya Ogi¹, Tetsu Hattori², Takahiko Higashi² and Yoshikazu Terai¹

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[17-P32]

Lattice Vibrational Properties of BaSi₂ Epitaxial Film in Polarized Raman Spectra

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[17-P33]

Size and Shape Control of Epitaxial β -FeSi $_2$ Nanodots in Si-based Nanoarchitecture Toward Advanced Thermoelectric Materials

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[17-P34]

The Growth of High Quality Epitaxial β-FeSi₂ Thin Films by Solid Phase Epitaxy Tatsuhiko Taniguchi¹, Shunya Sakane¹, Shunsuke Aoki¹, Kentaro Watanabe^{1,2}, Takeyuki Suzuki³, Takeshi Fujita^{2,4}, and Yoshiaki Nakamura^{1,2}

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[17-P35]

Solid Phase Epitaxy for Formation of Silicon-GaSb Based Heterostructures

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[17-P36]

Fe/boron-doped Ultrananocrystalline Diamond/Fe Trilayered Spin Valve Junctions Kazuki Kudo¹, Satoshi Takeichi¹, Hirokazu Kishimoto¹, Ken-ichiro Sakai², Hiroyuki Deguchi³, and Tsuyoshi Yoshitake¹

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[17-P37]

Structural Analysis of ErSi₂ Nanowire Grown on Si(100)

Kazuki Takahashi, Hiroyuki Kagitani, Shun Osaka, Hiroshi Tabata, Osamu Kubo, Mitsuhiro Katayama *Graduate School of Engineering, Osaka University, Japan*

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Oxidation Resistance of Impurity Doped Mg₂Si Grown from the Melt Shu Konno, Tsubasa Otubo, Kohei Nakano, Haruhiko Udono *Ibaraki University, Japan*

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Evaluation of a Bandgap of Cubic Mg₂Si by First Principle Calculation with PMT-QSGW Method Ayumi Inaba and Hiroharu Sugawara

Department of System Design, Tokyo Metropolitan University, Japan

[17-P40]

Frequency-Dependent Capacitance-Voltage and Conductance-Voltage Characteristics of n-Type Nanocrystalline FeSi₂/Intrinsic Si/p-Type Si Heterojunctions

Peeradon Onsee, Asanlaya Duangrawa, Sakmongkon Teakchaicum, Phongsaphak Sittimart, Adison Nopparuchikun and Nathaporn Promros

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[17-P41]

Surface Structure of Epitaxial BaSi₂(100) Film Formed on Si (111)

Hiroyuki Kagitani, Osamu Kubo, Shouta Okasaka, Kazuki Takahashi, Hiroshi Tabata, and Mitsuhiro Katayama

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Effects of Source Materials on Fabrication of β -FeSi₂ Thin Films by RDE Method Haruya Kobayashi, Keisuke Sato and Yoshiaki Hara National Institute of Technology, Ibaraki College, Japan

Effects of Nitrogen Doping on Optical and Electrical Properties of FeSi₂ Films Prepared by Sputtering Tomohiro Nogami¹, Ryuji Baba¹, Hirokazu Kishimoto¹, Tarek M. Mostafa¹, Nathaporn Promros², and Tsuyoshi Yoshitake¹ Department of Applied Science for Electronics and Materials, Kyushu University, Japan

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[17-P44]

EXAFS Study on Nitrogen-doped Nanocrystalline FeSi₂ Films Prepared by Sputtering Aki Tominaga^{1,2}, Ruji Baba¹ Hirokazu Kishimoto¹, Tarek Mostafa¹, Hiroshi Naragino¹, Kazutaka Kamitani², Toshihiro Okajima³, and Tsuyoshi Yoshitake¹

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[17-P45]

Solvent-Controlled Anatase Titania Thin Film via Hydrothermal Method and Its Orientation Mechanism Meilan Guo^{1,2}, Tianguo Deng¹, Jun Tao¹, Yun Gao¹ and Guosheng Shao^{2,3}

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[17-P46]

Ab-initio Calculations of Nanocrystallites Embedding in Silicon: Optical Properties Semyon A. Balagan¹, Vladimir U. Nazarov² and Nikolay G. Galkin¹

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Forming of Magnesium and Calcium Silicide Nanoparticles on the Surface of Hydrogenated Silicon Thin Films for the Whole in Situ Deposition Process of Diodes

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